Amendment and Response

Applicant: Norman L. Oberski et al.

Serial No.: 10/6232,848 Filed: July 18, 2003 Docket No.: A126.113.102

Title: INSPECTION TOOL WITH A 3D POINT SENSOR TO DEVELOP A FOCUS MAP

IN THE ABSTRACT

Please replace the paragraph beginning at page 9, line 4, with the following, re-written paragraph:

Abstract of the Disclosure

An inspection system, and process for use thereof, allows for inspecting of semiconductors or like substrates. The inspection system keeps-includes an inspection device and an auxiliary sensor. The auxiliary sensor aids in the focus of focusing the sensor-inspection device within the depth of field of the lens used. The system specifically uses the process of making a separate pass over the wafer surface using a 3D point sensor before the inspection of the wafer begins.